

[10191/3399]

**REPLY UNDER 37 C.F.R. § 1.116  
EXPEDITED PROCEDURE  
GROUP ART UNIT 1765**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

DO NOT ENTER

Appl. No. : 10/691,108 Confirmation No. 4772  
Applicant : Klaus BREITSCHWERDT  
Filed : October 22, 2003  
Title : DEVICE AND METHOD FOR ANISOTROPIC PLASMA ETCHING  
OF A SUBSTRATE, PARTICULARLY A SILICON ELEMENT  
TC/A.U. : 1765  
Examiner : Lan Vinh

LV

1/19/07

Mail Stop AF  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**REPLY UNDER 37 C.F.R. § 1.116**

Sir:

In response to the Final Office Action of August 8, 2006, please amend the above-captioned application without prejudice as follows.

**Amendments to the Claims** are reflected in the listing of claims, which begins on page 2 of this paper

**Remarks** begin on page 4 of this paper.